

高頻高壓半導世界

_GaN可靠嗎？找歪伯理論

Reliability of GaN Power Devices

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瑞典軍品管上校歪伯

- Waloddi Weibull 瑞典军人数学家
- 年纪轻轻就去了海军，表现优异，结果很快一路升到上校
- 他发明了用爆震波侦探海底海底物质的数学模式，目前海洋探测石油，就是用他发明的方法
- 1939年他更发表了**Weibull Distribution**
 - 当时瑞典军部及武器制造商(Bofors)就是用他发明的品管方式来保证瑞士武器制造精良(當時世界一流)



W. Weibull 1887-1979

photo: Sam C. Saunders, Pullman WA, USA

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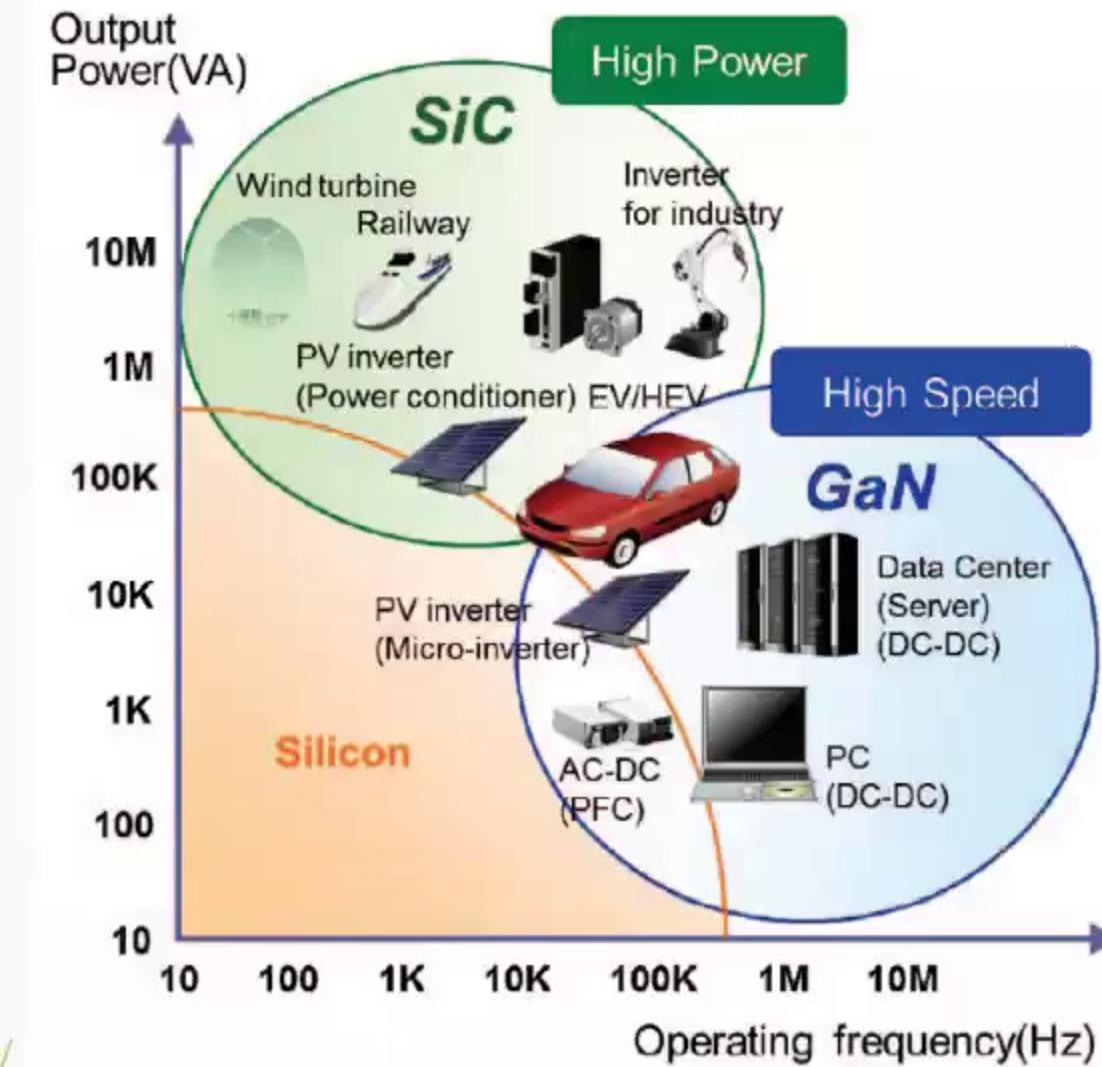
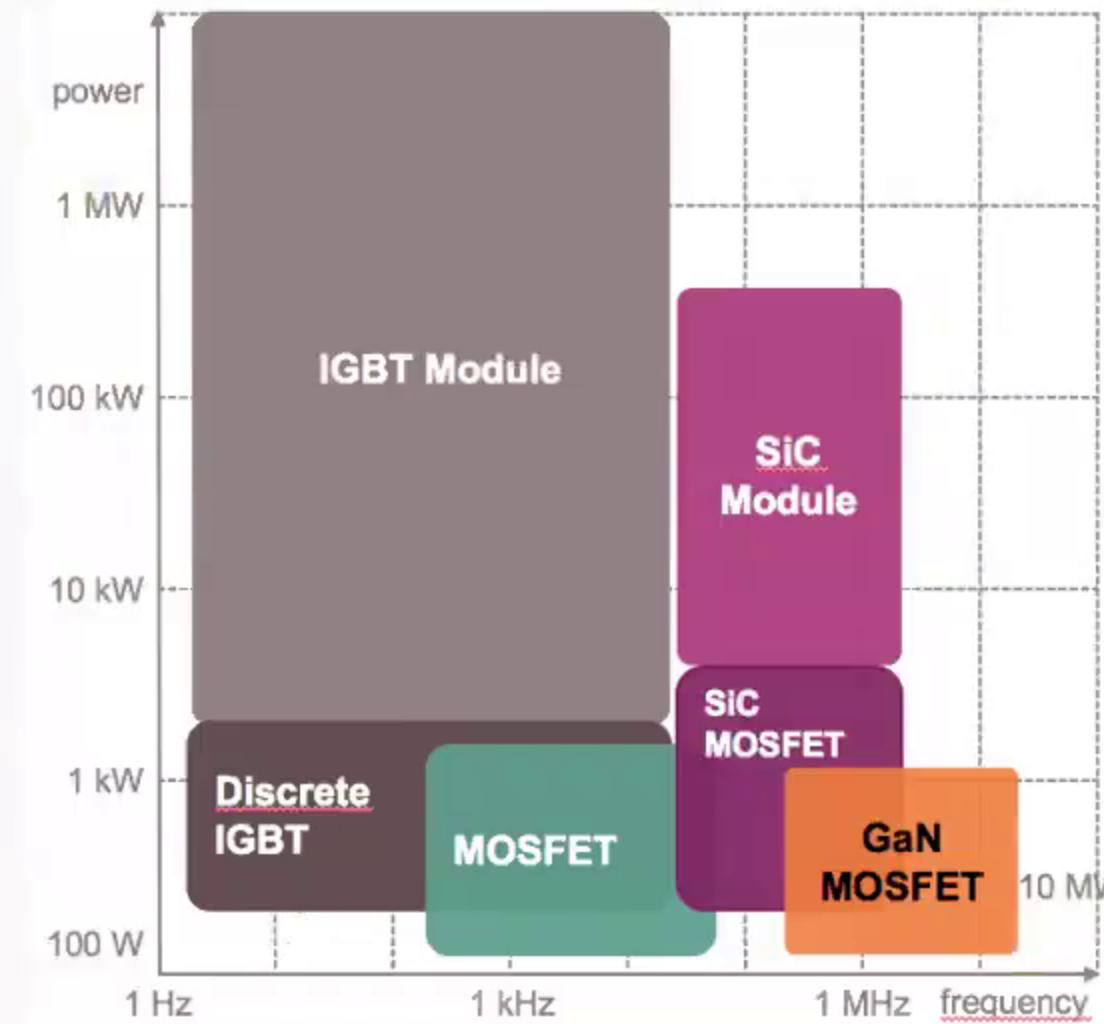
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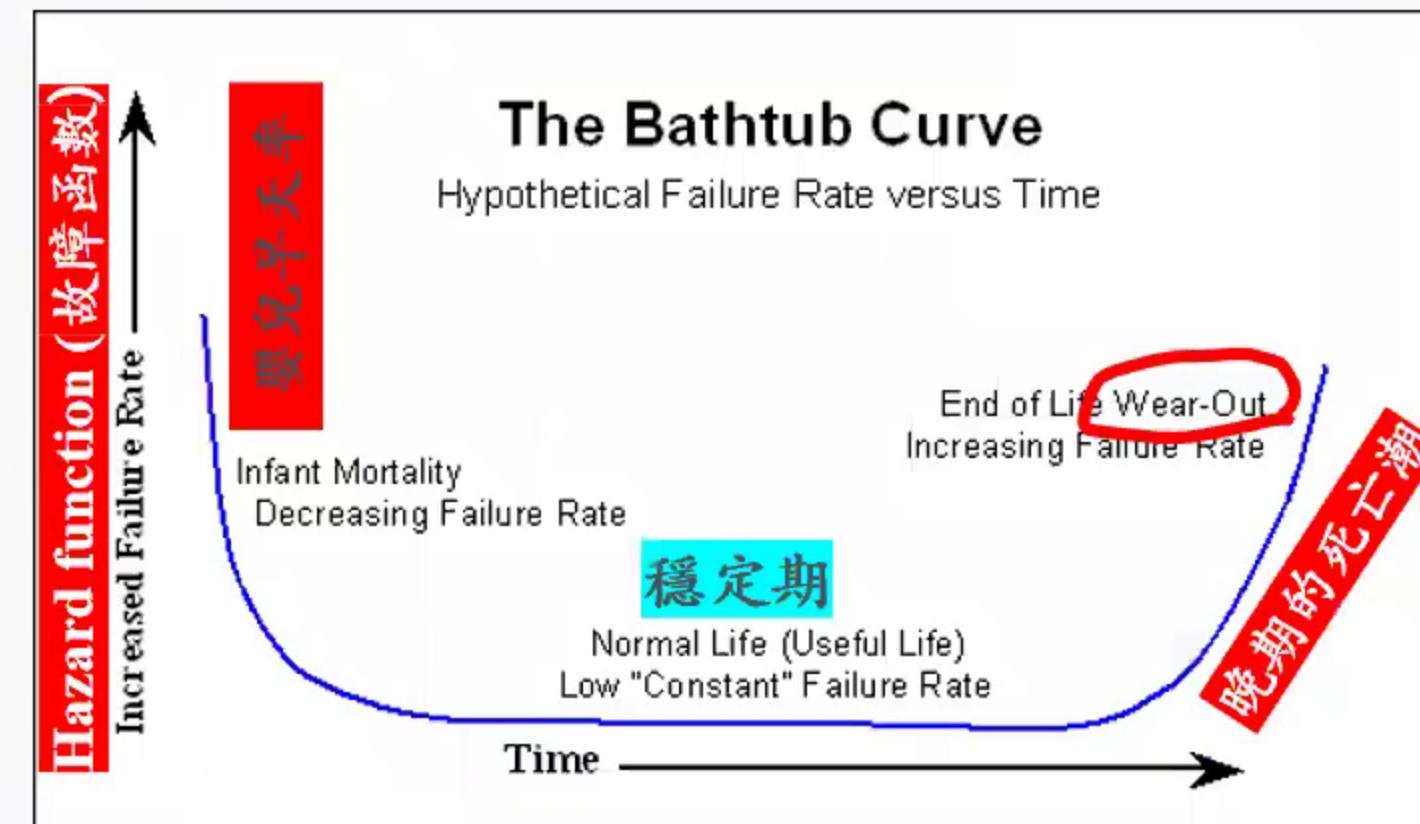
GaN拔劍四顧心不茫



<https://semiengineering.com/improving-reliability-for-gan-and-sic/>

歪伯愛洗澡：产品可靠性澡盆曲线

- 一般像樣产品的生命週期大概都是有澡盆形狀(如右)
 - 早期的产品失敗率叫做"早死早超生"或曰"嬰兒早夭率" (**infant mortality**)
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<https://www.weibull.com/hotwire/issue21/hottopics21.htm>

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Weibull Distribution: 可靠性分析很給力

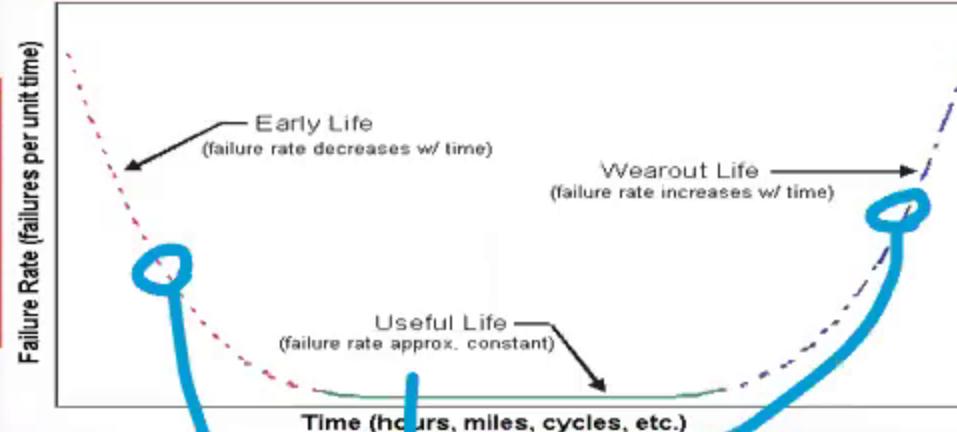
- 所屬PDF (probability density distribution)

$$f(T) = \frac{\beta}{\eta} \left(\frac{T-\gamma}{\eta}\right)^{\beta-1} e^{-\left(\frac{T-\gamma}{\eta}\right)^\beta}$$

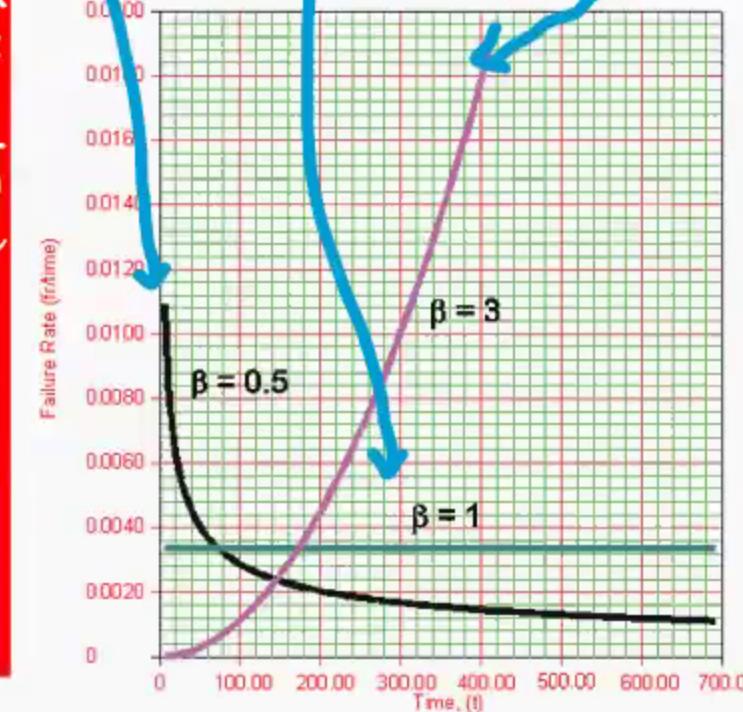
- β = shape parameter (形狀參數)
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- 歪伯厲害的地方就是用他以他發明的概率密度函數(PDF)推導出適當的**故障函数**，竟能解釋产品可靠性澡盆曲线所有部分

(故障函数)



Hazard function (故障函数)



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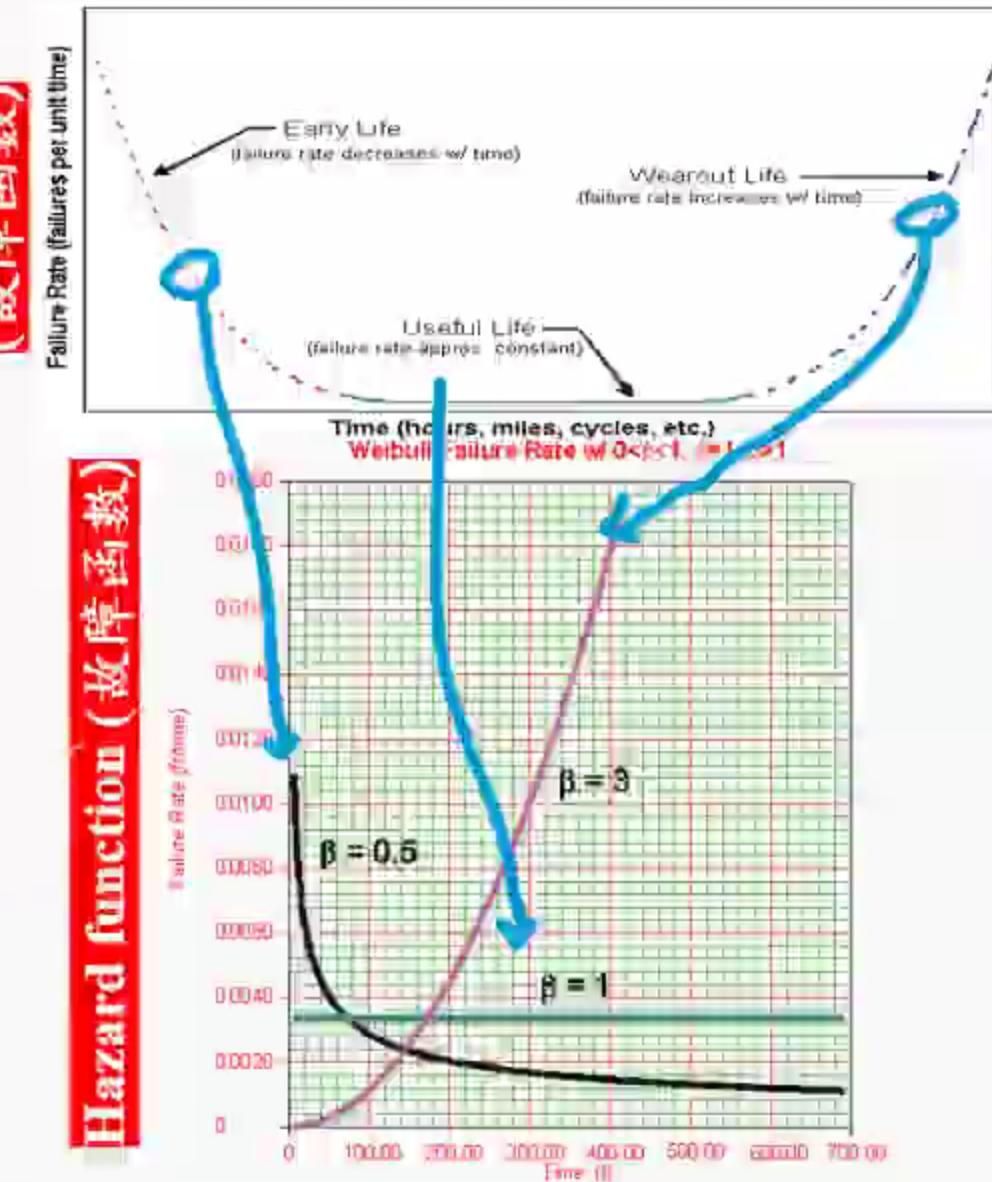
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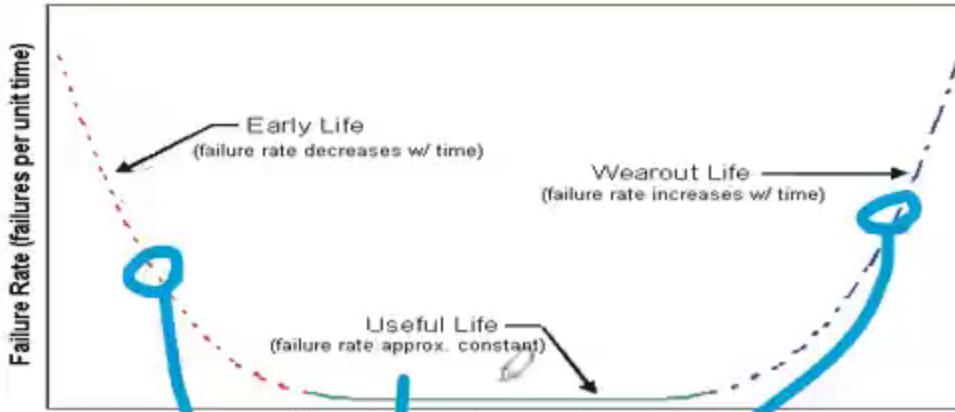
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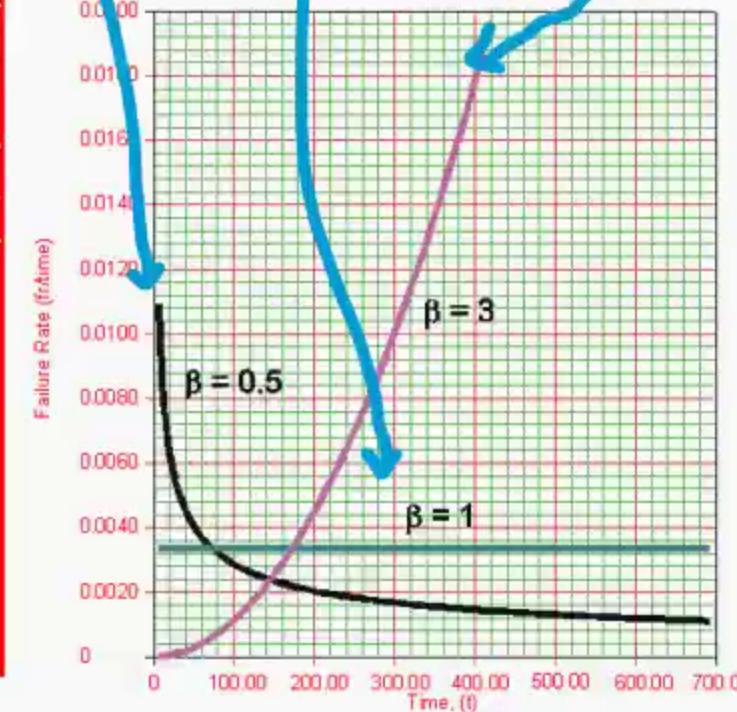
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(故障函数)



Hazard function (故障函数)



$\beta < 1$ (夭折死): 2016 三星 Note 7

三星终向中国消费者低头Note7全面召回!

- 8月2日，三星Note7欧美地区开售
- 8月24日，全球首炸(早夭)
- 10月11日，三星终于宣布也在中國召回全部Note7手机，共计190984台，中国消费者也得到了与全球一样的待遇

Note7 手機下架共損失54億美元

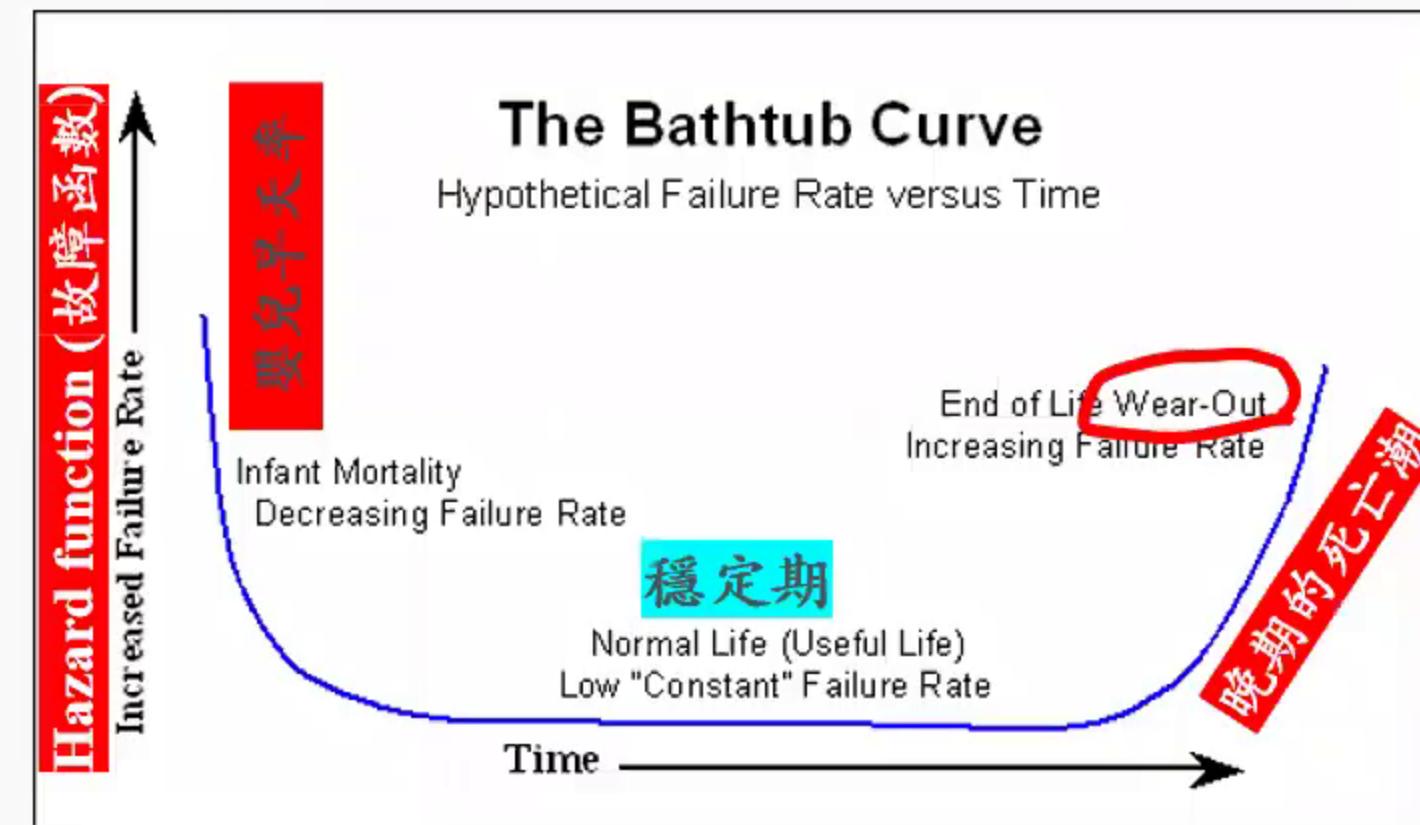
- 三星想要赶在iPhone之前，匆忙出货



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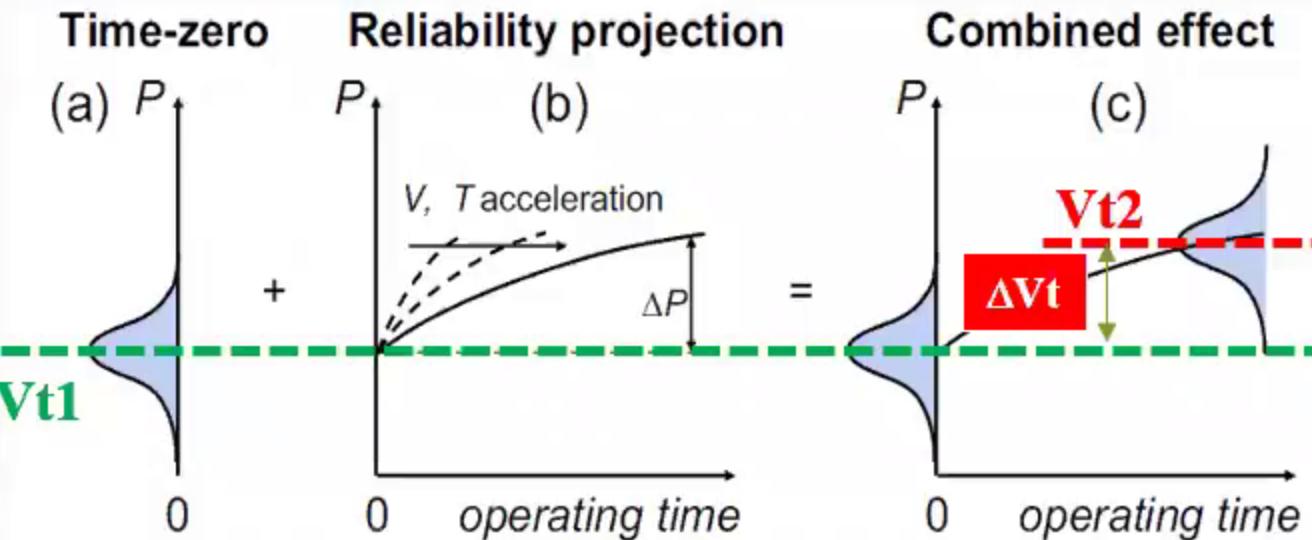
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Si-CMOS的可靠性分析參數

- Si-CMOS內某重要電性參數(P)因時間及使用，就如同輪胎一般，開始有老化漂移現象，例如 $P = V_t$, V_t shift = ΔV_t

- 我們知道 $I_d \propto (V_g - V_t)^2$, 若 $V_g = 0.7V$, $V_{t1} = 0.3V$, 老化漂移後 $V_{t2} = 0.35V$, $\Delta V_t = 50mV$, $I_{d2} = 0.765I_{d1}$, 元件就算拜拜了

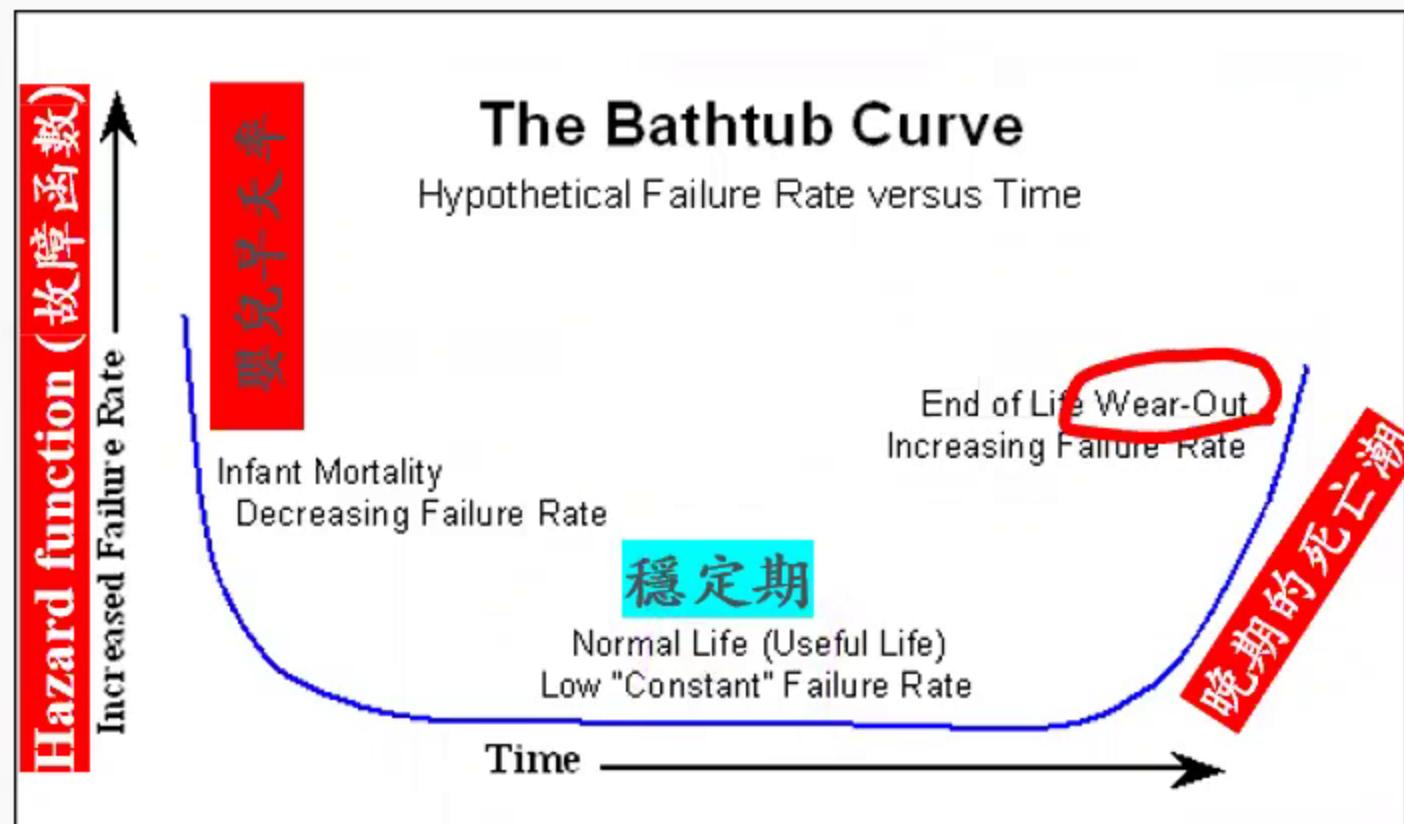
- 基本上，我們要求電子元10年內，只能容許 $\Delta V_t = 50mV$
 - 但我們卻沒有10年可以等啊！



The defect-centric perspective of device and circuit reliability—From gate oxide defects to circuits, B. Kaczer et al., Solid-State Electronics 125 (2016) 52–62

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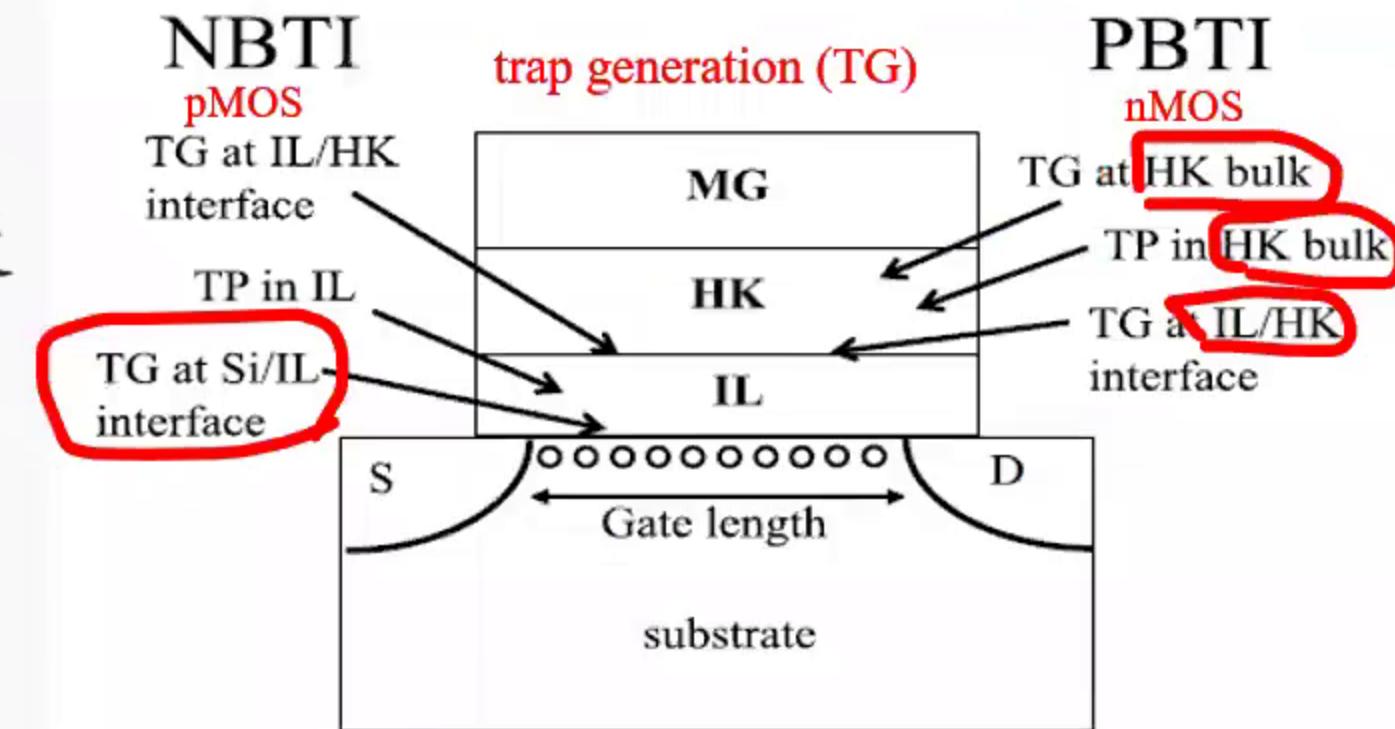


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Si-CMOS的可靠性分析參數

- 电子老化漂移當然由內部最脆弱的地方開始，例如
- Negative-bias temperature instability(NBTI) 负偏置温度不稳定性是影响阈值电压 V_t 的偏移，其乃因Silicon IL界面太脆弱(dangling bonds)，解决方法為以重氢(D_2)重拳出击(high temperature deuterium anneal, ~1000C)，界面得以强化也(這制程之优化，竟耗费Intel/IBM數年)

Mukhopadhyay et al, "A Comparative Study of NBTI and PBTI Using Different Experimental Techniques," in TED, 63(10)4038-4045, 2016

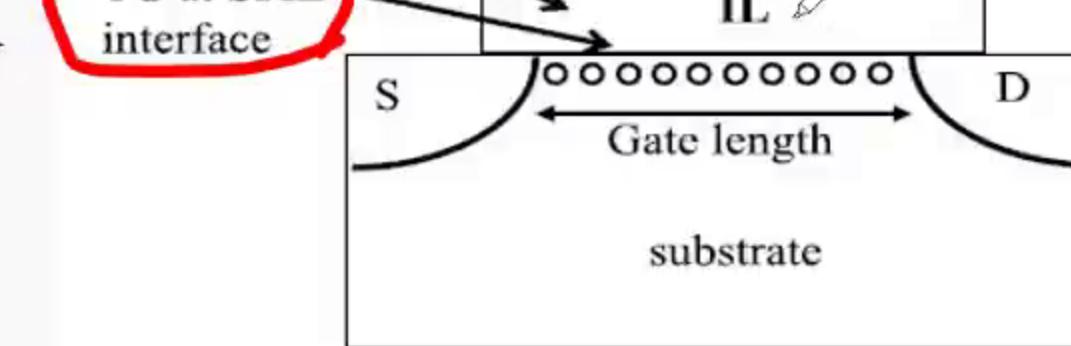
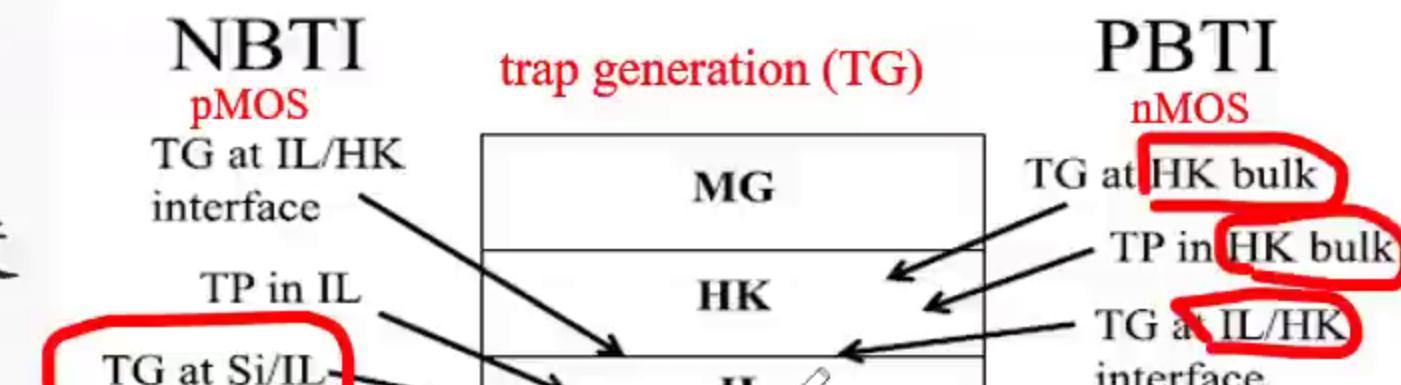


RELIABILITY ENGINEERING
IN RF CMOS, Guido T. Sasse

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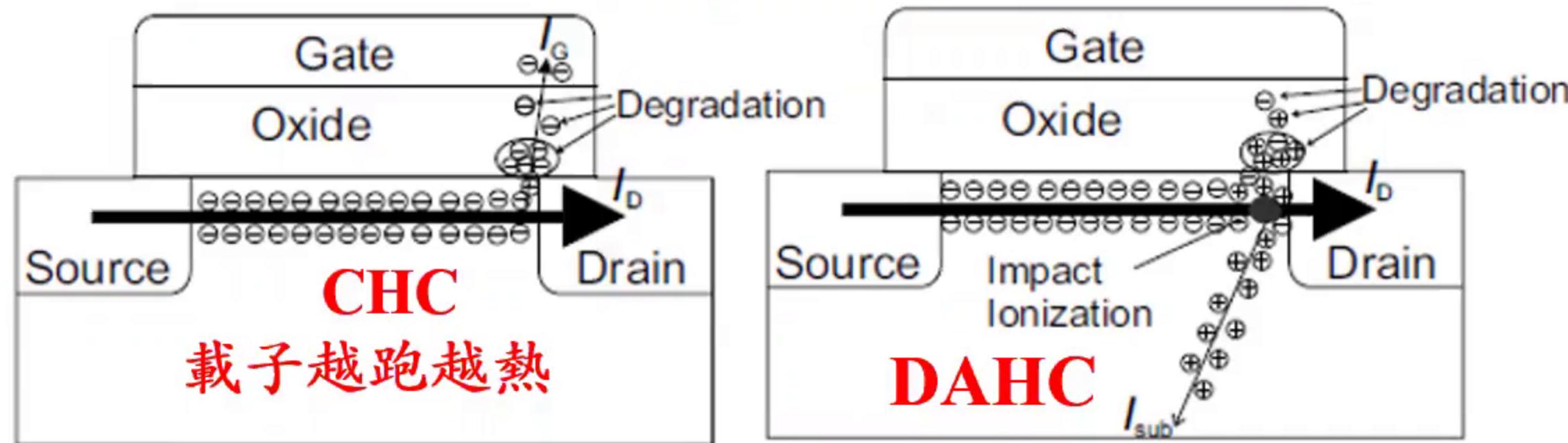
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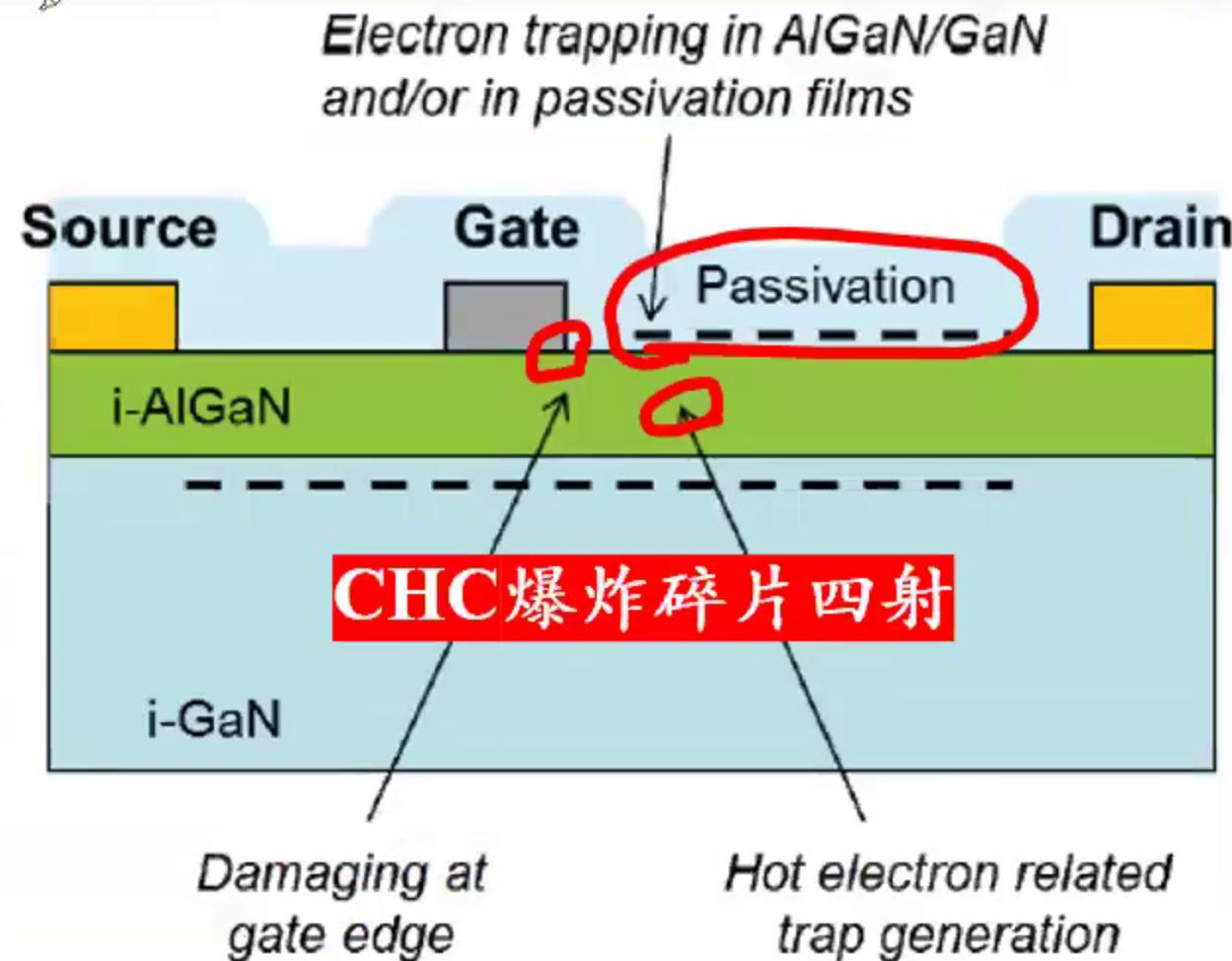
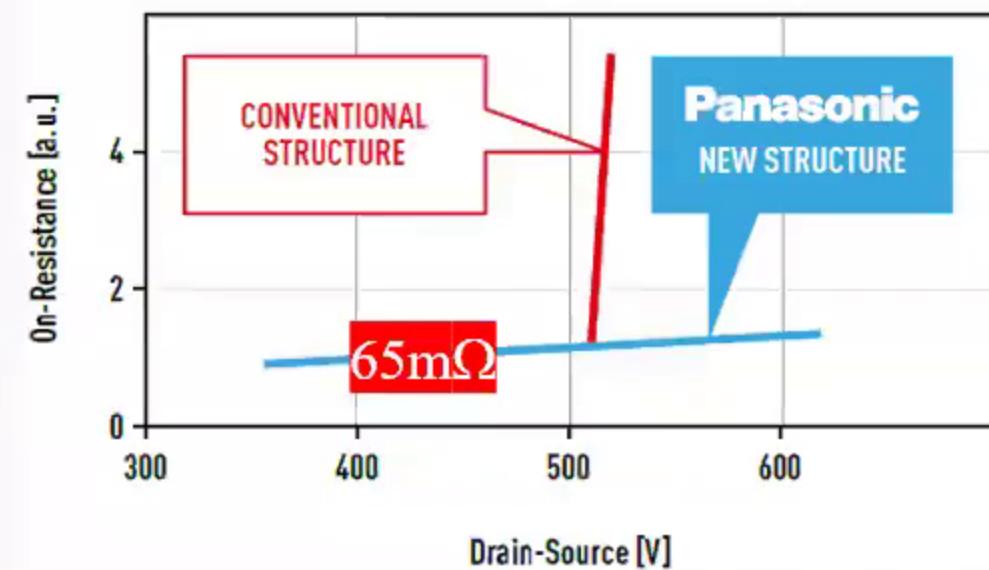
被加速到自爆: Channel Hot Carriers (CHC)

- 电子見到 V_{DS} 立馬興奮从Source衝向Drain，越跑越快(故動能分布好似溫度越來越高，所以曰之Hot)，在近終点處竟翻車爆炸了(Drain的电場太強)
- 爆炸碎片四射，傷及一堆池魚，包括oxide, gate, Interfaces，及Drain漏电雪崩 (Drain Avalanche Hot Carriers, DAHC)等



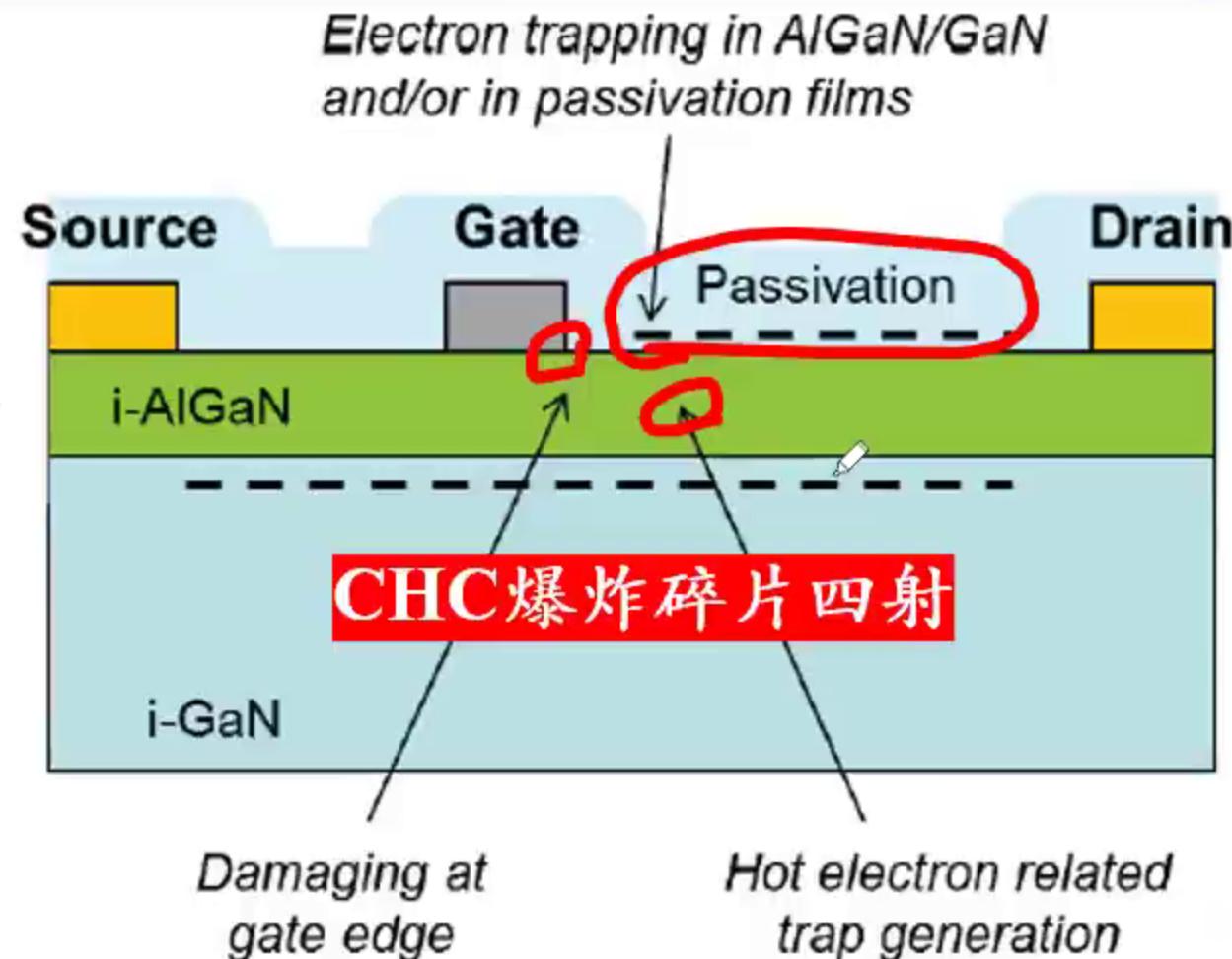
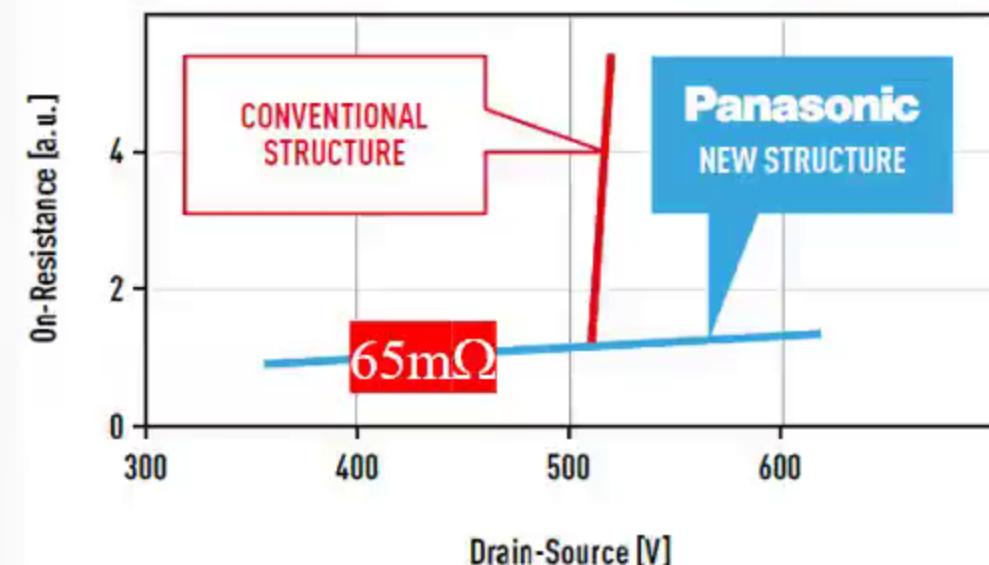
Reliability Issues in GaN Power Devices

- 前面Si-CMOS，我們舉了個 $P=Vt$ 的例子，但在GaN power devices, $P = \text{On-Resistance (current collapse)}$,
- 左下图所示，电阻突然在 $V_D > 500V$ 時，瞬間拔高(电流消失了)，怎麼回事？原來是一個**CHC效應**(右图)，



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業界可靠性測試標準 JEDEC: JEP180.01

- GUIDELINE FOR SWITCHING
RELIABILITY EVALUATION
PROCEDURES FOR GALLIUM
NITRIDE POWER
CONVERSION DEVICES**

<https://www.jedec.org/standards-documents/docs/jep18001>

Table 2 — DHTOL recommendations

Stress name	Abbrev.	Conditions	Requirements	
			# Lots / units per lot	Duration / Acceptance
Dynamic High Temperature Operating Life	DHTOL	Maximum recommended switching conditions ¹⁾ (Table 3)	3 Lots X ≥ 8 test beds of core-cells. (2)	1000h ¹⁾ / 0 Fails

1) Test conditions can exceed the maximum recommended ones to increase the equivalent application runtime at customer-use conditions. Until industry confidence is built in the model, durations shorter than 1000h would need agreement of the user.
2) A core cell is defined as the basic switching cell, clause 4.6

Table 3 — Best-practice DHTOL conditions

Stress parameter	Conditions	Example
DC bus voltage	Maximum recommended V_{DS} or 80% of absolute maximum V_{DS} per datasheet	480V (600V abs. max.)
Operating junction temperature	Worst case temperature, T_J , within datasheet operating limits	$80^{\circ}\text{C} \leq T_J \leq 125^{\circ}\text{C}$ represents the typical expected temperature range in application. In case of supporting data T_J shall be set to be the worst case for the technology
Peak current	Corresponding to the maximum power condition	Technology/product dependent Test chamber dependent (in particular cooling limited)
Switching frequency	Max allowable for the desired operating junction temperature	e.g., 100kHz for hard-switching application.
Gate driving conditions	As recommended by manufacturer in datasheet and application note	Technology/product dependent

業界可靠性測試標準 JEDEC的歪伯精神

- 當然我們也希望GaN产品的生命週期像個很長的澡盆(如右)
- 意思是說，將制程優化改進，使得**wear Out**能越晚來到越好
- 又除了JEDEC，還有AEC
 - [http://www.aecouncil.com/AECD documents.html](http://www.aecouncil.com/AECD/documents.html)

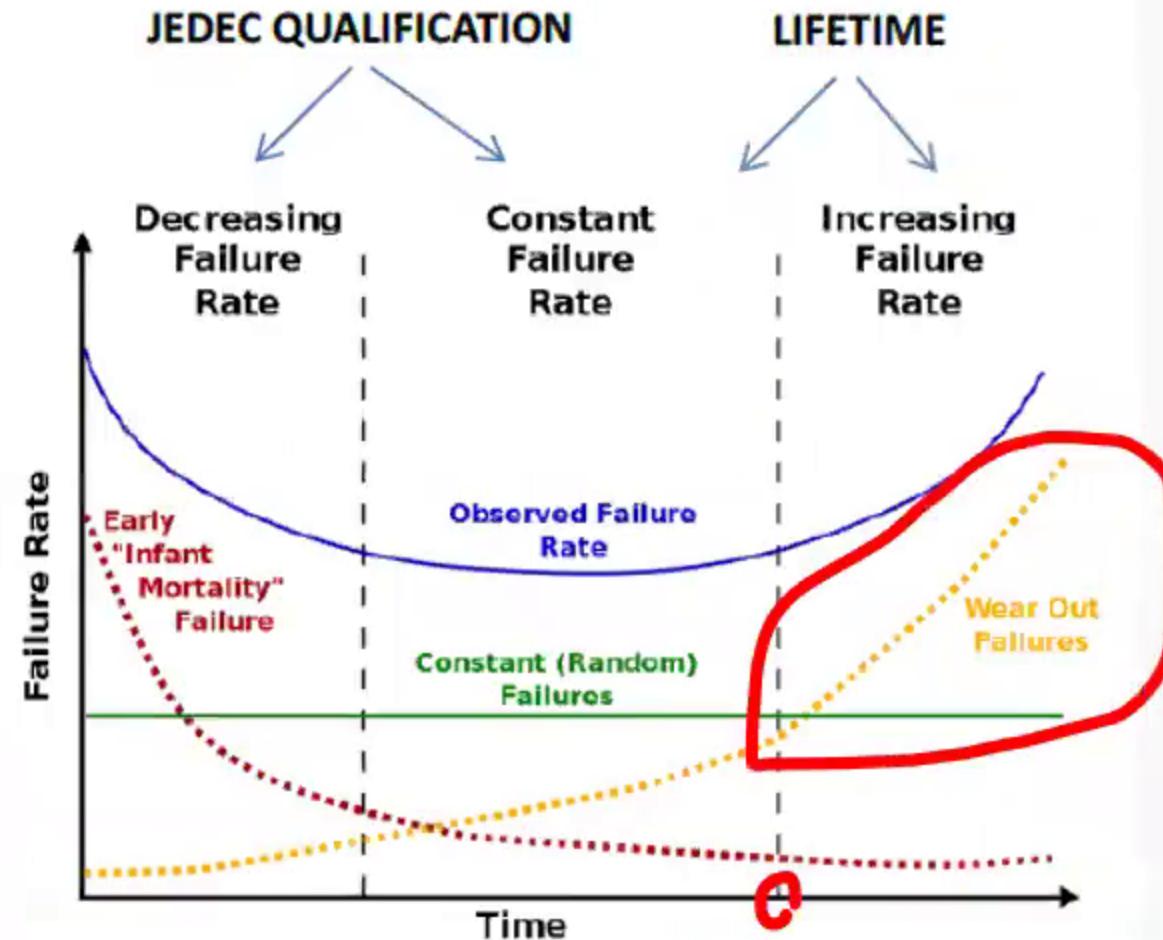


Figure 1. Reliability lifecycle illustrated using a "bathtub curve"

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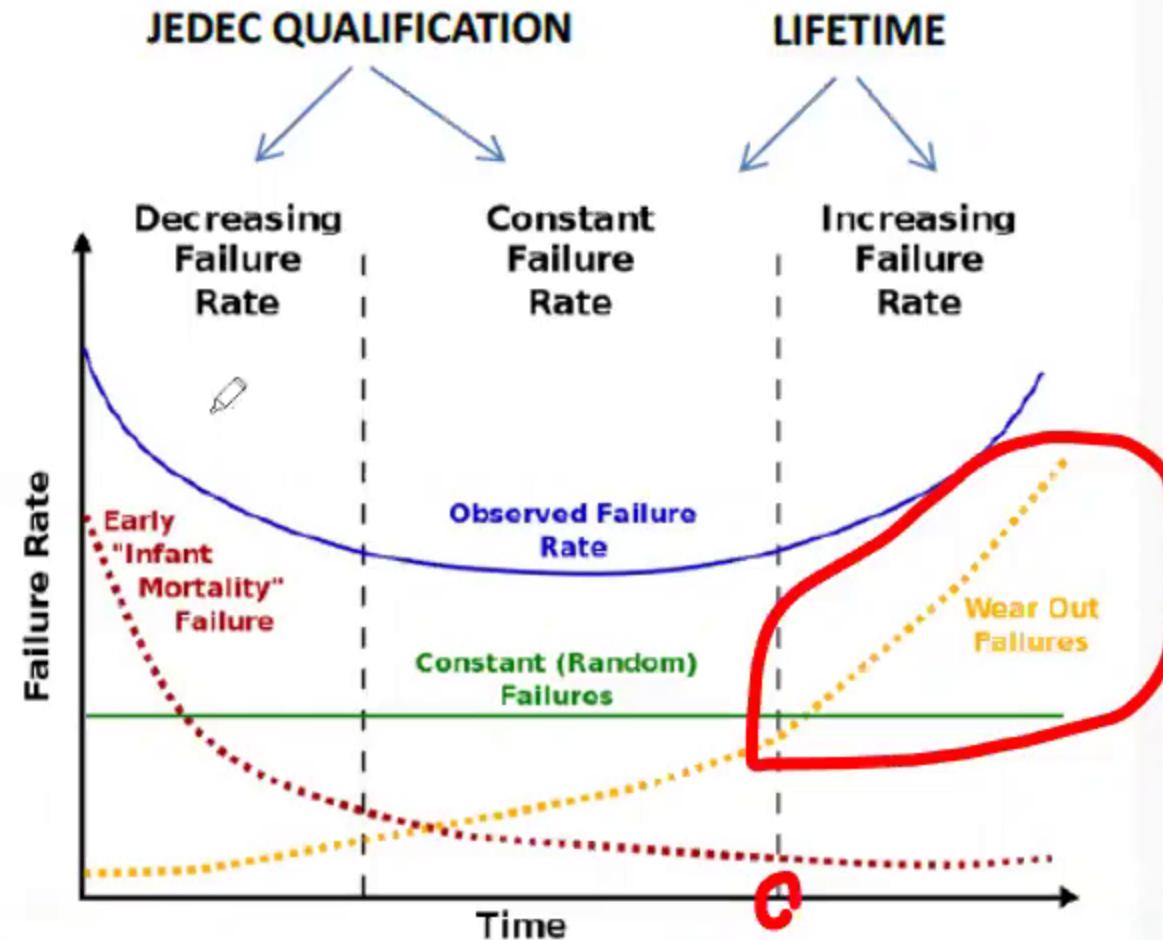


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JEP180.01之實戰演例

Table 1. JEDEC qualification test results for Transphorm's products

Test	Symbol	Conditions	Sample	Pass Criteria
High Temperature Reverse Bias	HTRB	TJ=150°C VDS = 480V 1000 Hrs	3 lots 77 parts per lot 231 total parts	0 Fails
Highly Accelerated Temp and Humidity Test	HAST	130°C 85% RH 33.3 PSI Bias = 100V 96 Hrs	3 lots 77 parts per lot 231 total parts	0 Fails
Temperature Cycle	TC	-55°C / 150°C 2 Cycles / HR 1000 Cycles	3 lots 77 parts per lot 231 total parts	0 Fails
Power Cycle	PC	25°C / 150°C $\Delta T = 100^\circ\text{C}$ 7500 Cycles	3 lots 77 parts per lot 231 total parts	0 Fails
High Temperature Storage Life	HTSL	150°C 1000 Hrs	3 lots 77 parts per lot 231 total parts	0 Fails

HTRB: High Temperature Reverse Bias

- 但我們卻沒有**10年**可以等啊!所以加熱加電壓**加速測試**(HTRB)
 - 加熱(125C-150C)
 - 加電壓(指的是加高電壓 V_{DS} ,而 V_{GS} 必須為零),
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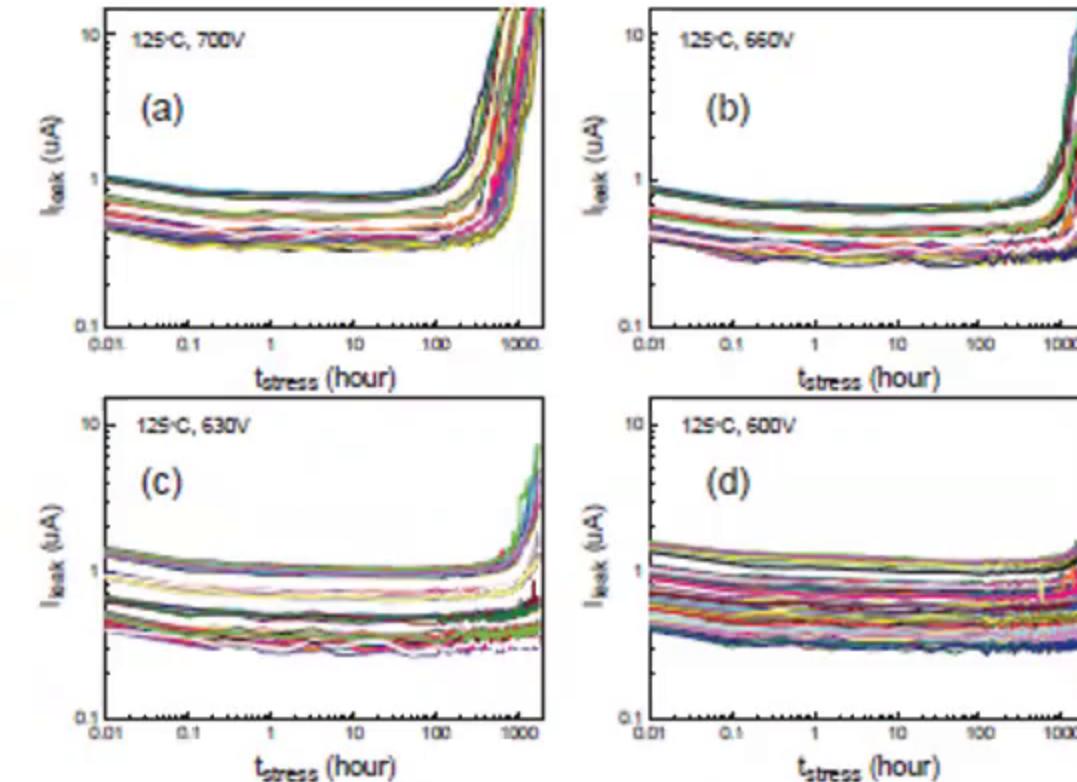
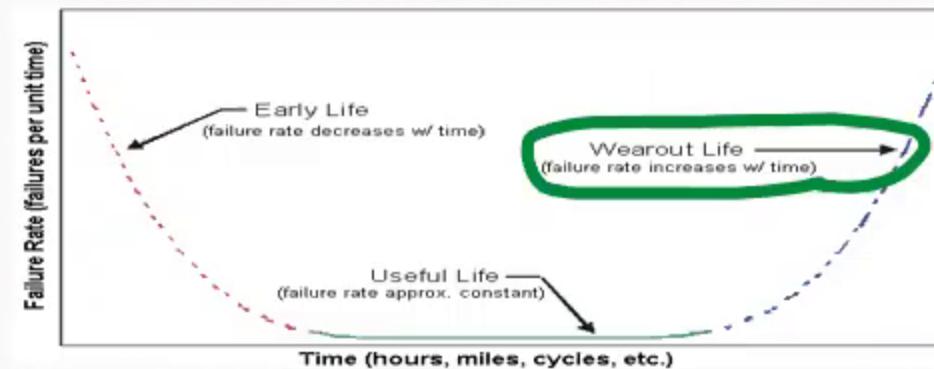


Fig. 2: OFF-state ($V_{GS}=0\text{V}$) drain leakage current of HD-GIT at V_{DS} of 600V (I_{leak}) as a function of the total stress time t_{stress} . The stress bias voltage: (a) $V_{DS}=700\text{V}$, (b) $V_{DS}=660\text{V}$ (c) $V_{DS}=630\text{V}$, and (d) $V_{DS}=600\text{V}$.

K. Tanaka et al., "Reliability of hybrid-drain-embedded gate injection transistor," IRPS'17, pp. 4B-2.1-4B-2.10,

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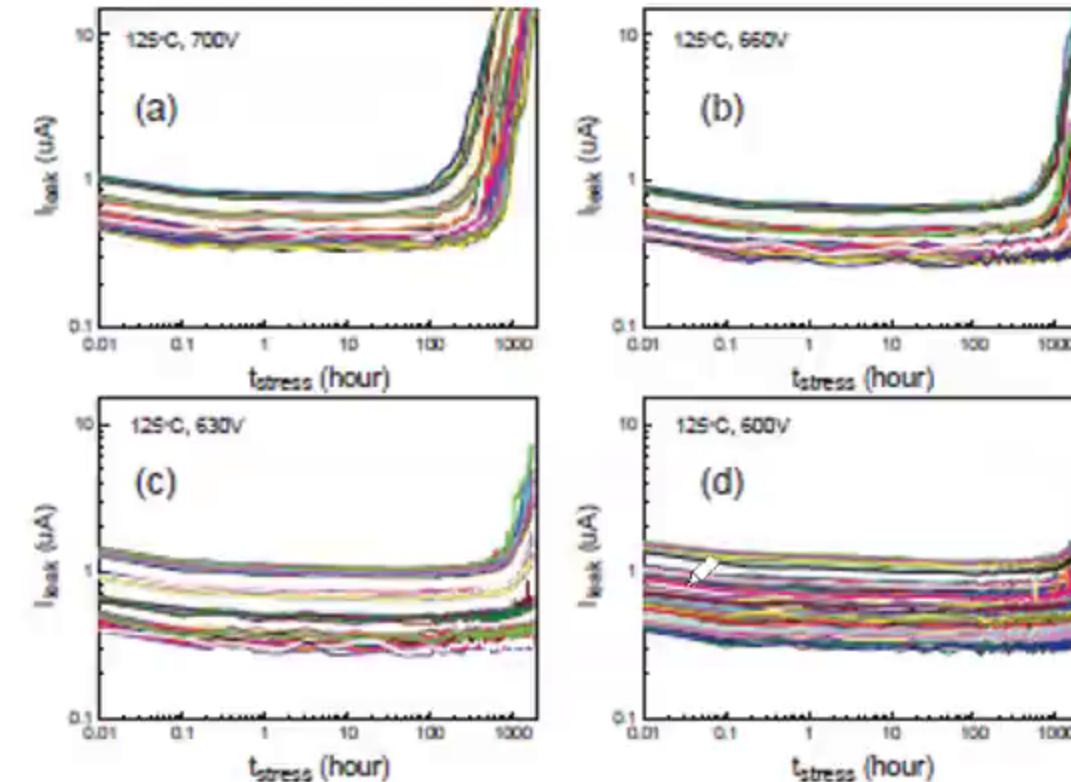
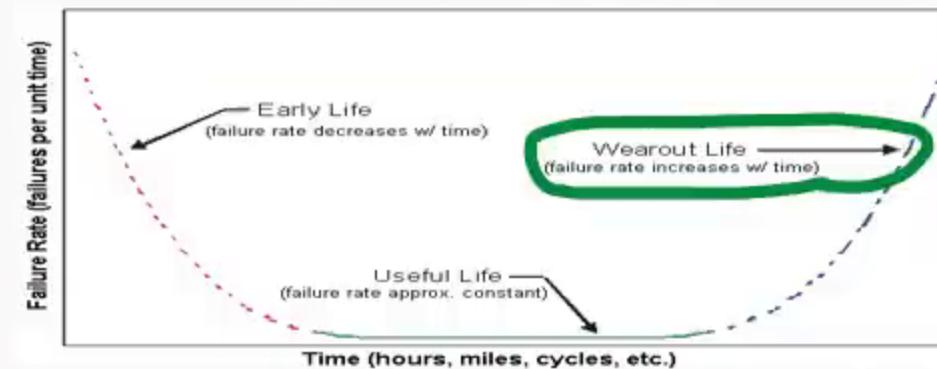


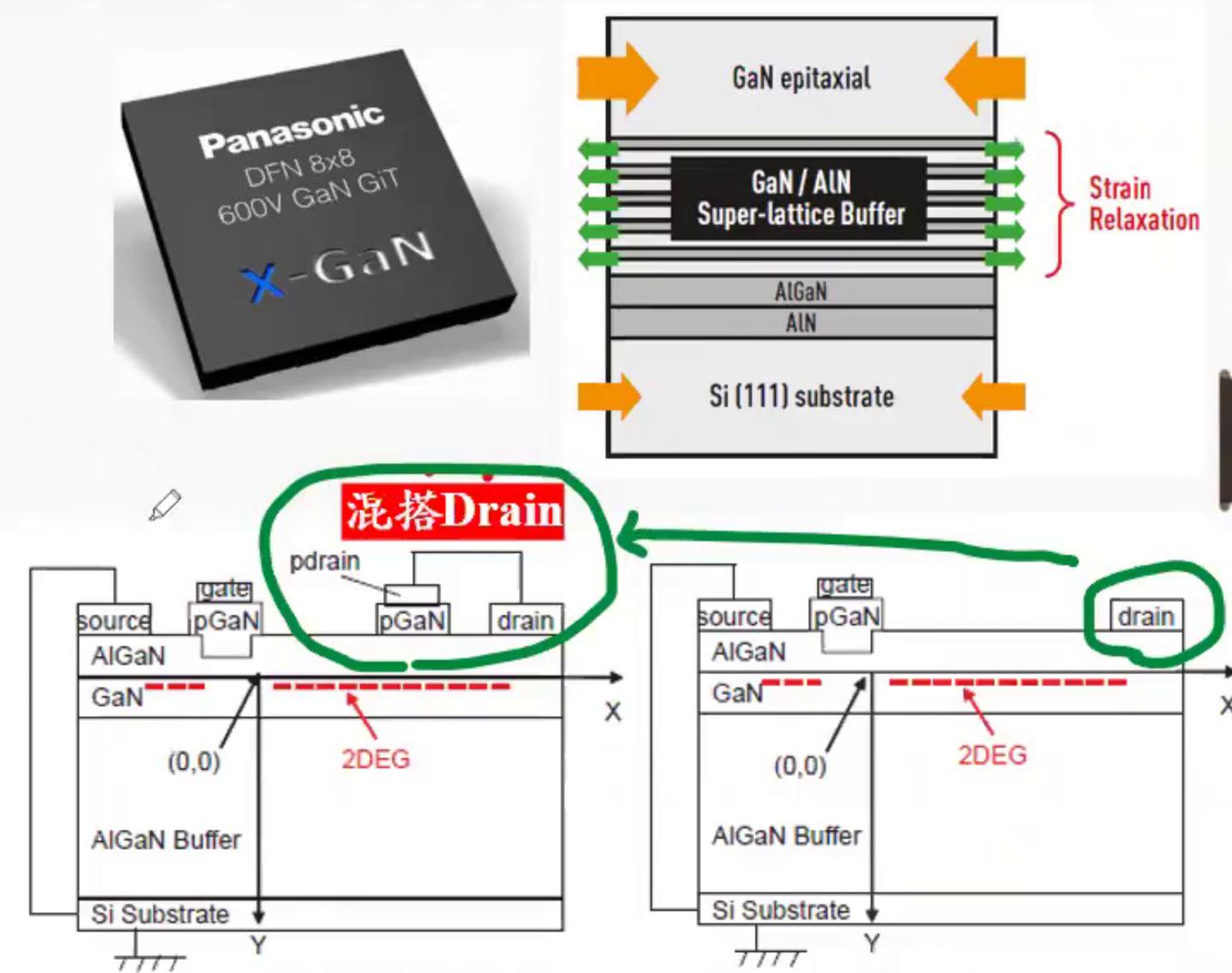
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JEP180.01夠不夠勁？

Panasonic說不夠勁，X-GaN

- 優化超晶格(superlattice)制程，
GaN磊晶加厚，調整carbon
doping等→ reduce deep traps
and stress free→ 減少CHC的
不良反應
- 混搭Drain, Hybrid-Drain
GiT (gate injection transistor),
push Vd to > 600V **no fails** (本
來~500V就掛了)



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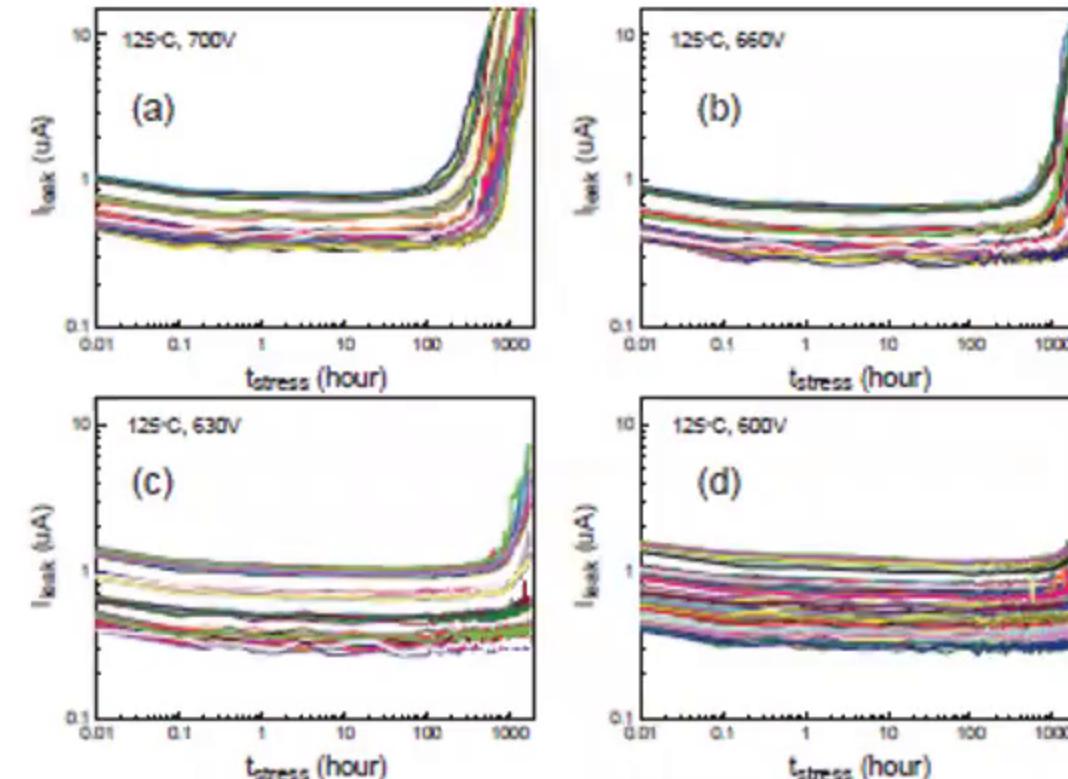
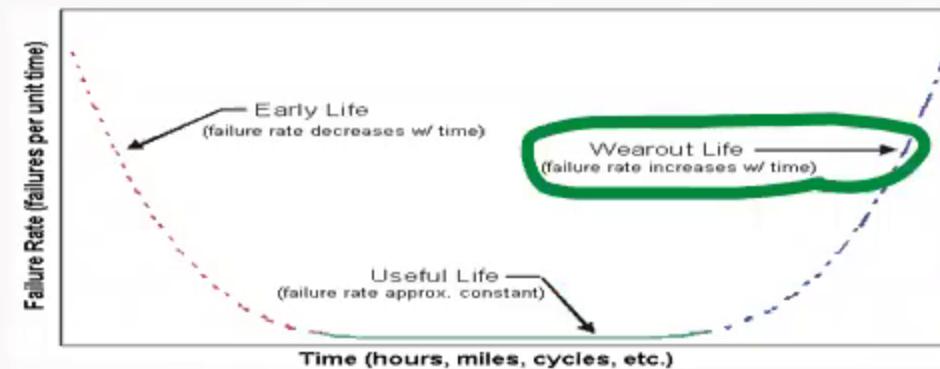
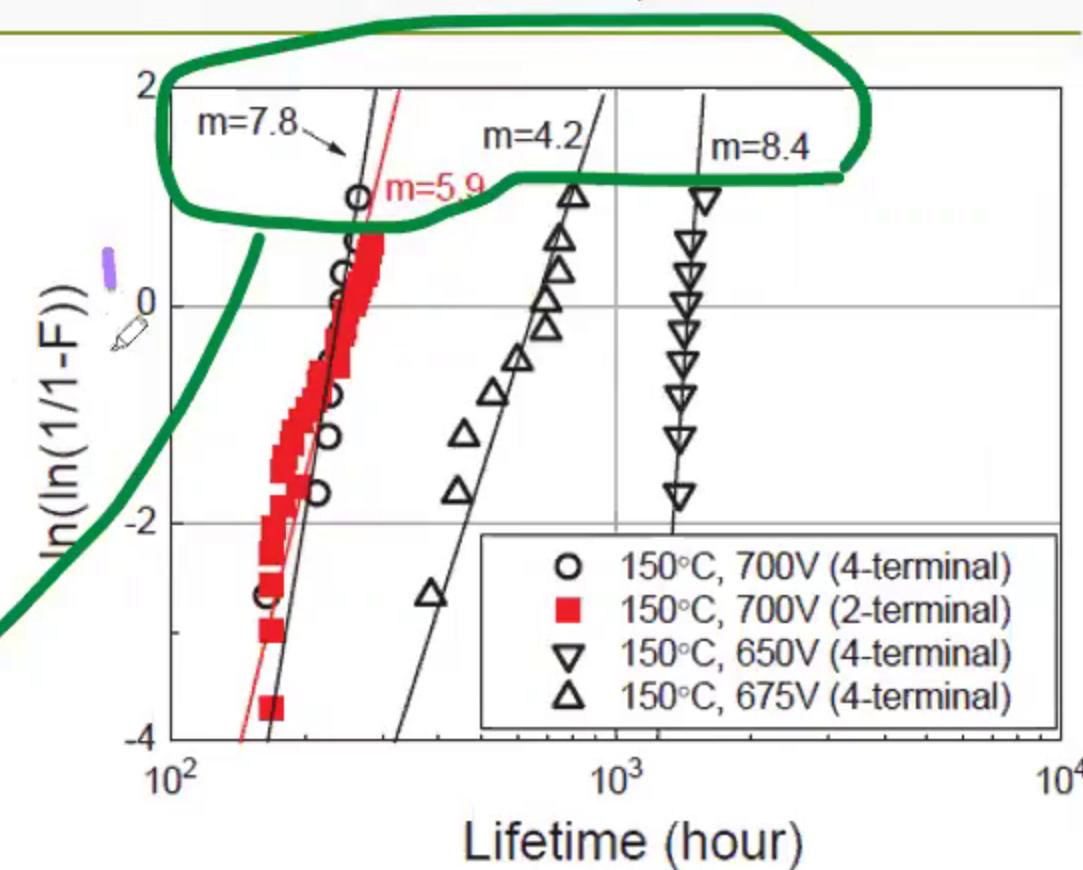
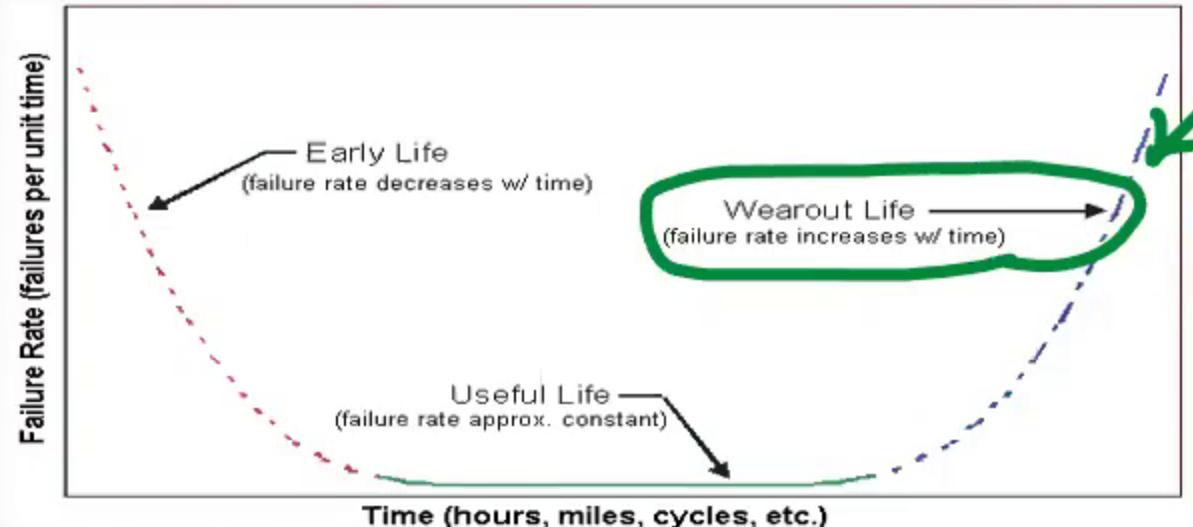


Fig. 2: OFF-state ($V_{GS}=0V$) drain leakage current of HD-GIT at V_{DS} of 600V (I_{leak}) as a function of the total stress time t_{stress} . The stress bias voltage: (a) $V_{DS}=700V$, (b) $V_{DS}=660V$ (c) $V_{DS}=630V$, and (d) $V_{DS}=600V$.

K. Tanaka et al., "Reliability of hybrid-drain-embedded gate injection transistor," IRPS'17, pp. 4B-2.1-4B-2.10,

Hybrid-Drain GiT的歪伯分布

- 歪伯分析發現，其 $\beta (= m) \gg 1$ ，此明顯的是**wear out**（叫做慢慢累死，乃正常的現象，沒有**surprise**，好耶！）



歪伯愛洗澡：产品可靠性澡盆曲线

Weibull Distribution: 可靠性分析很給力

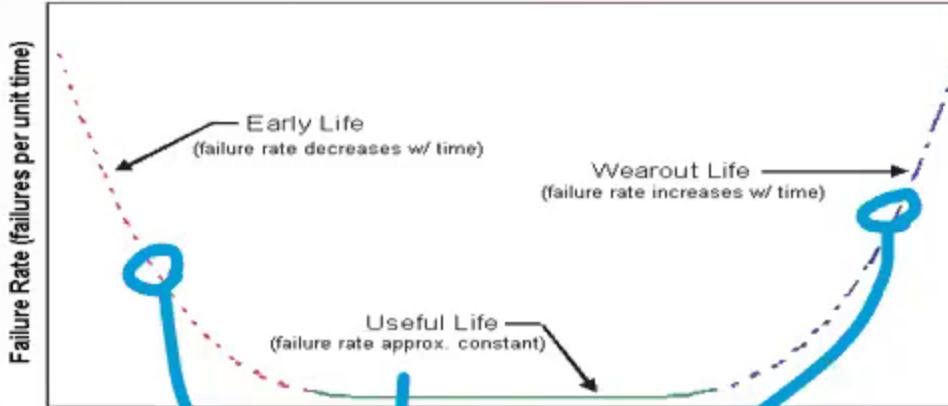
- 所屬PDF (probability density distribution)

$$f(T) = \frac{\beta}{\eta} \left(\frac{T-\gamma}{\eta}\right)^{\beta-1} e^{-\left(\frac{T-\gamma}{\eta}\right)^\beta}$$

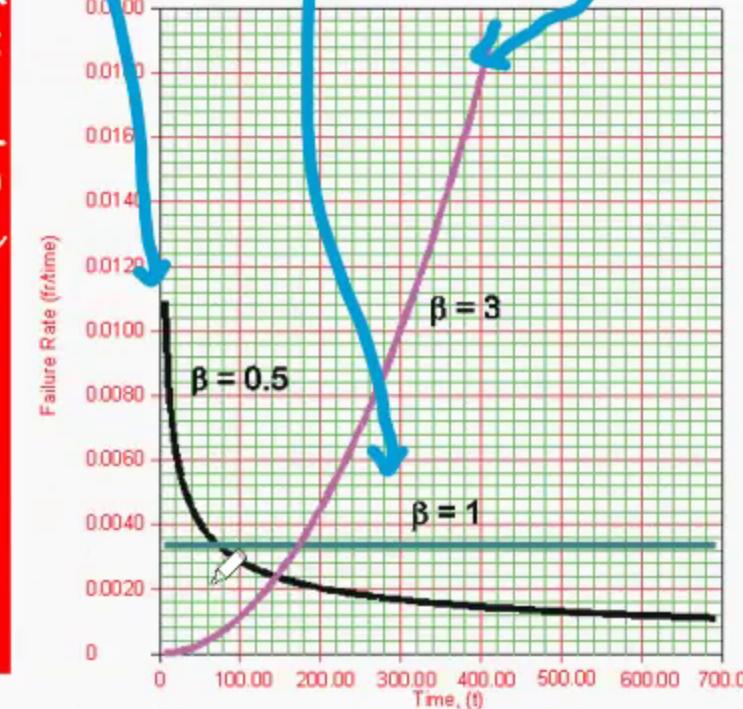
- β = shape parameter (形狀參數)
- η = scale parameter (比例参数)
- γ = location parameter (thresh in Minitab)

- 歪伯厲害的地方就是用他以他發明的概率密度函数(PDF)推导出適當的故障函数，竟能解釋产品可靠性澡盆曲线所有部分

(故障函数)



Hazard function (故障函数)

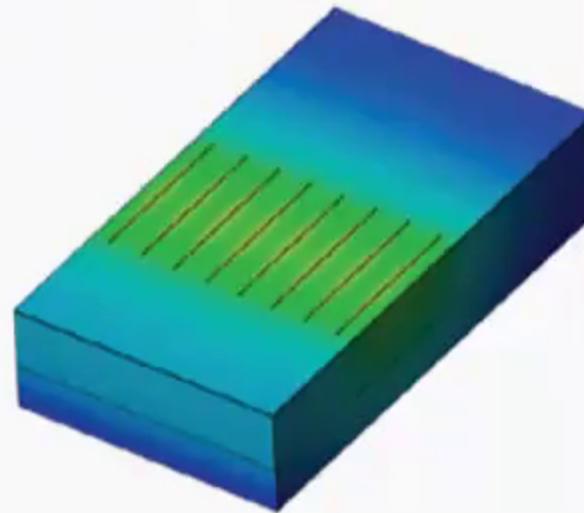
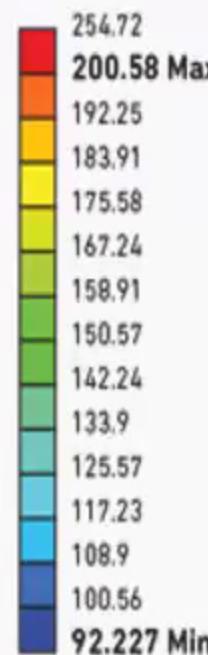


GaN on SiC更可靠，當然也更貴了

GaN on SiC

VS.

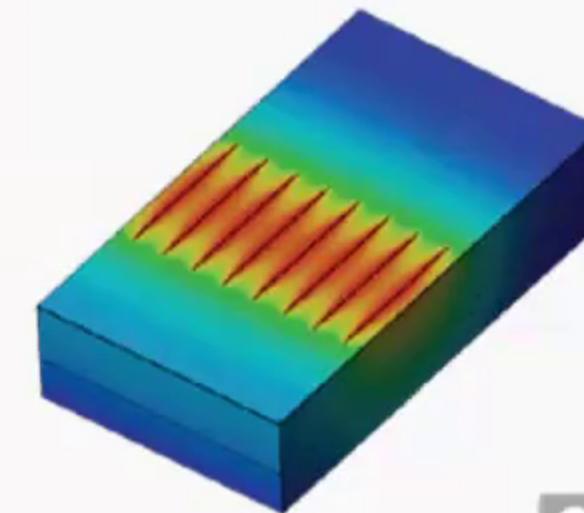
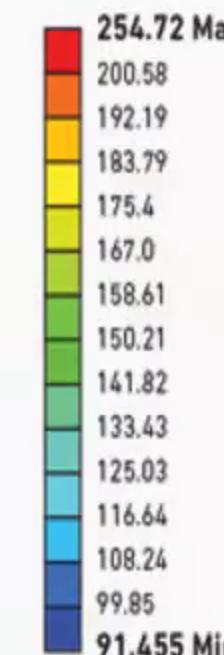
GaN on Si



54°C HOTTER
than GaN on SiC

27% HIGHER
CHANNEL TEMPERATURE

10 to 100X DECREASE
in device life



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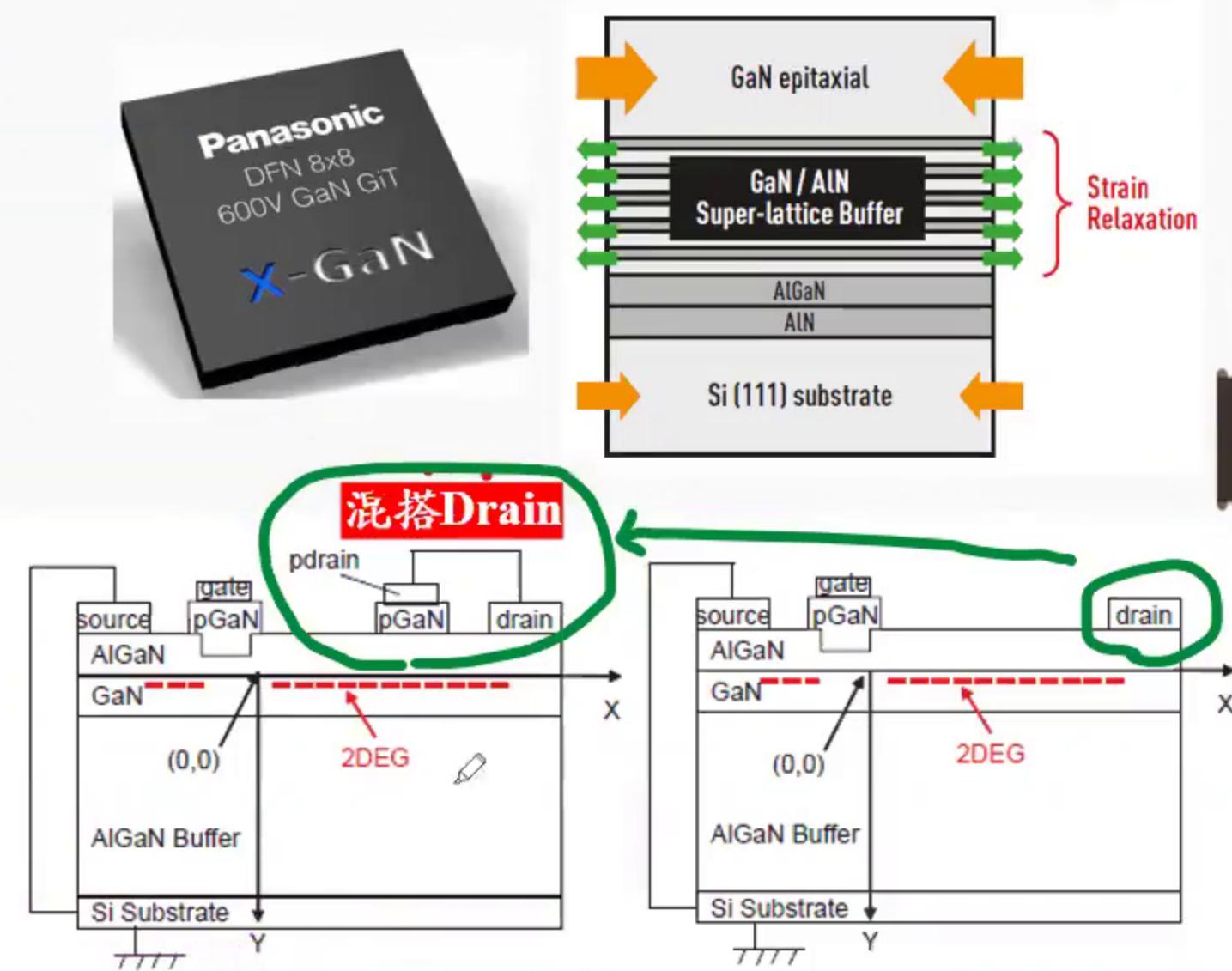


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JEP180.01夠不夠勁？

Panasonic說不夠勁，X-GaN

- 優化超晶格(superlattice)制程，
GaN磊晶加厚，調整carbon
doping等→ reduce deep traps
and stress free→ 減少CHC的
不良反應
- 混搭Drain, Hybrid-Drain
GiT (gate injection transistor),
push Vd to > 600V no fails (本
來~500V就掛了)



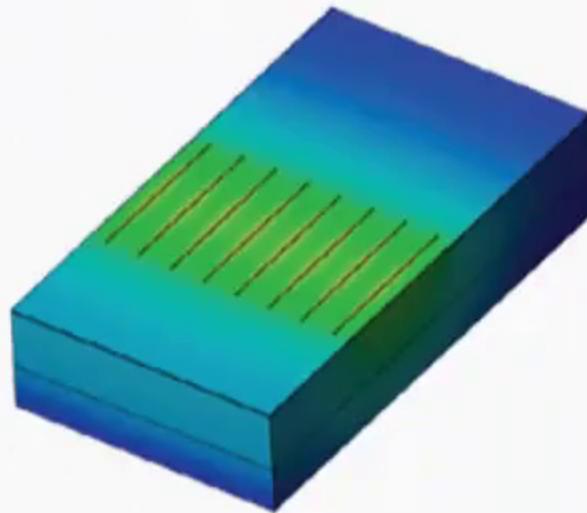
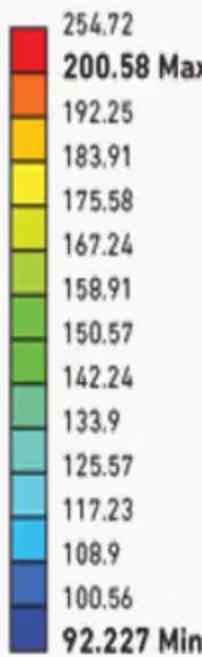
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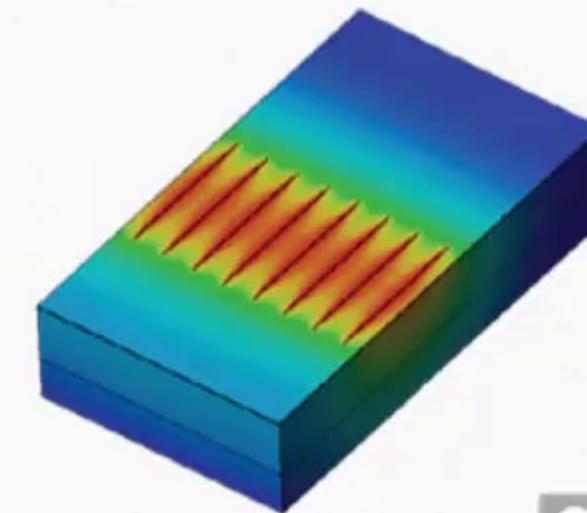
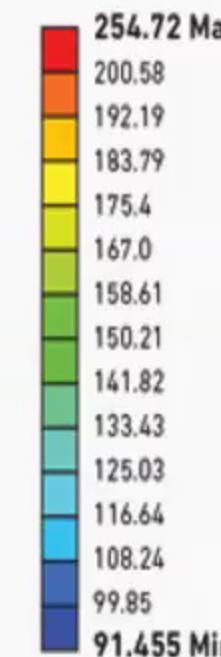
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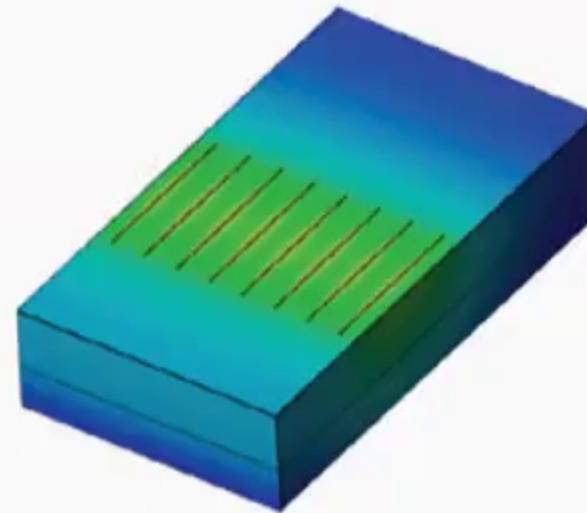
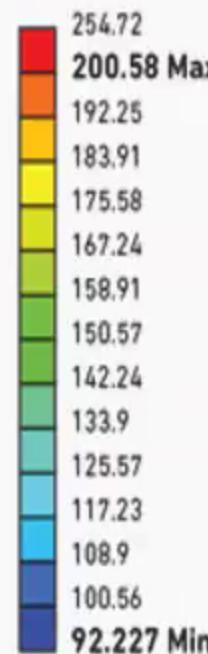
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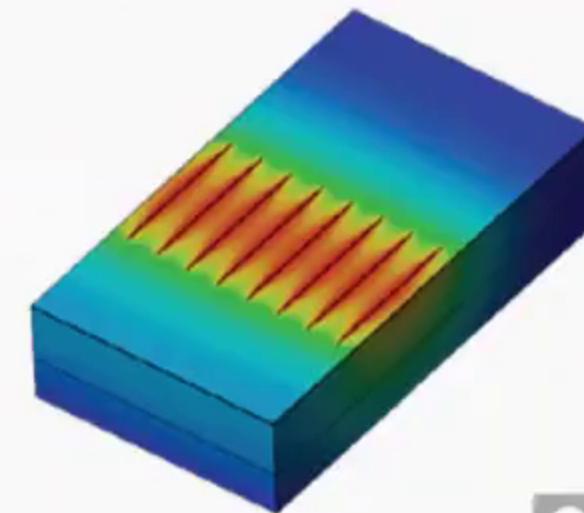
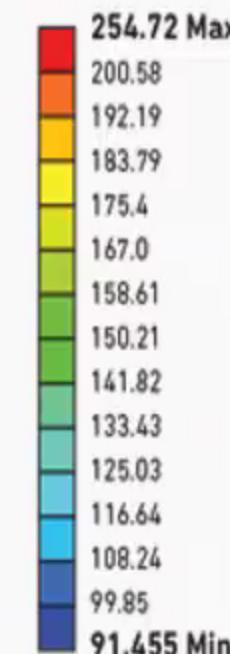
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高頻高壓半導世界

_GaN可靠嗎？找歪伯理論

Reliability of GaN Power Devices

王不老說半導